

Table 1

Experimental conditions of channel doping
with respect to the silicon-containing amorphous semiconductor film

substrate No.	chemical oxide film	diborane dilution ratio
1	None	0.1%B ₂ H ₆ /H ₂
2	Exist	0.1%B ₂ H ₆ /H ₂
3	None	1.0%B ₂ H ₆ /H ₂
4	Exist	1.0%B ₂ H ₆ /H ₂

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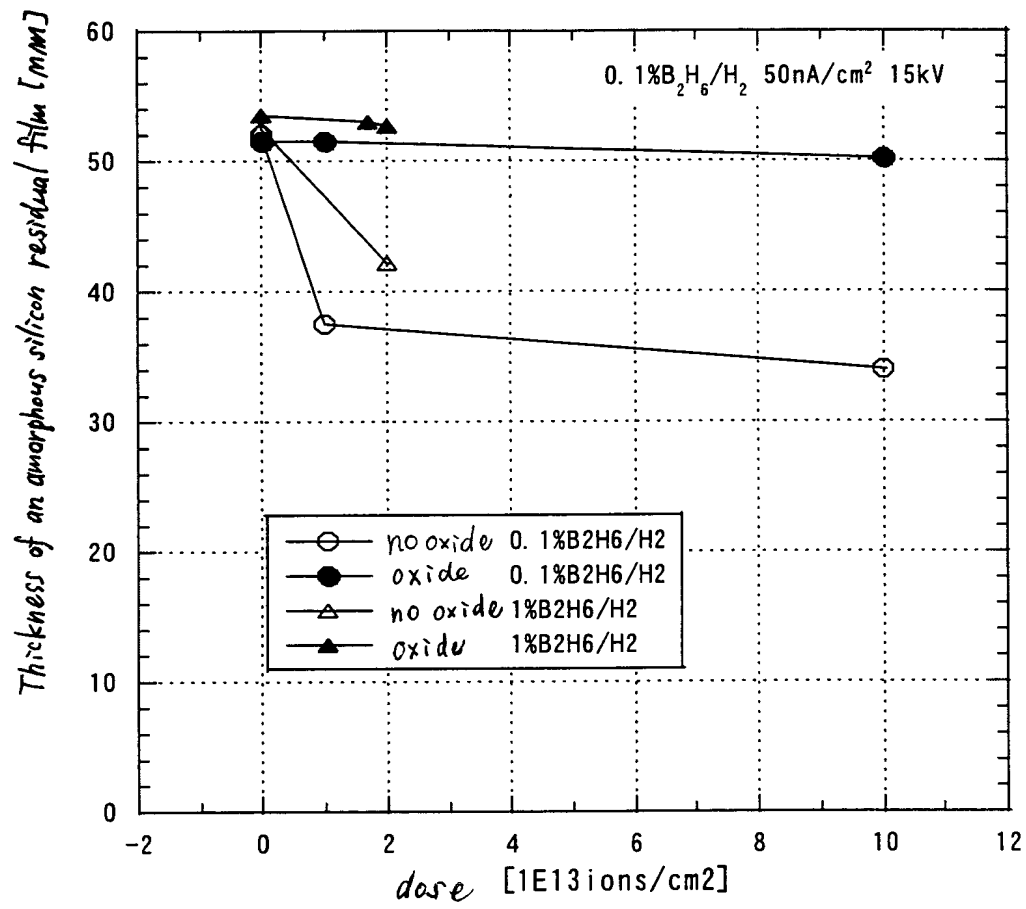


Fig. 1

Fig. 2A

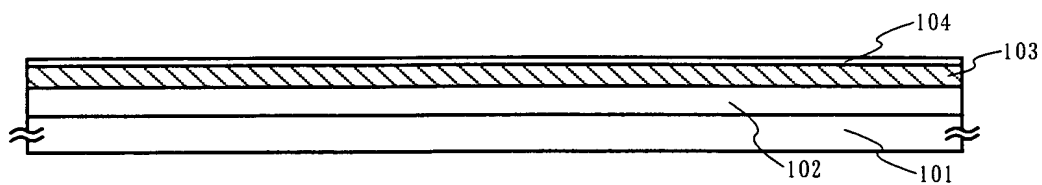


Fig. 2B

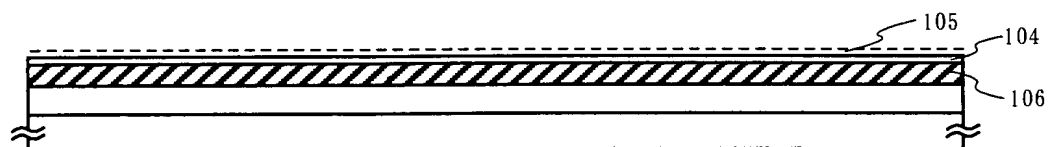


Fig. 2C

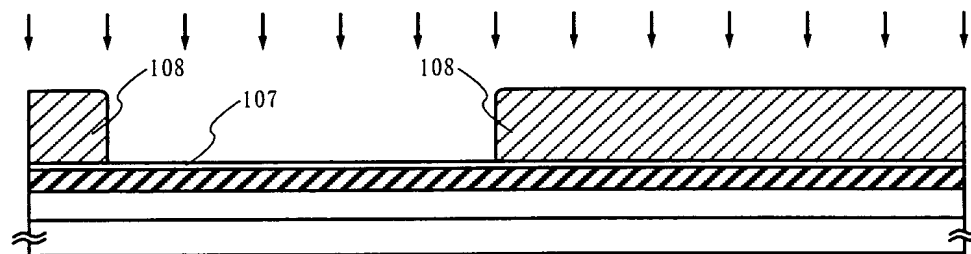


Fig. 2D

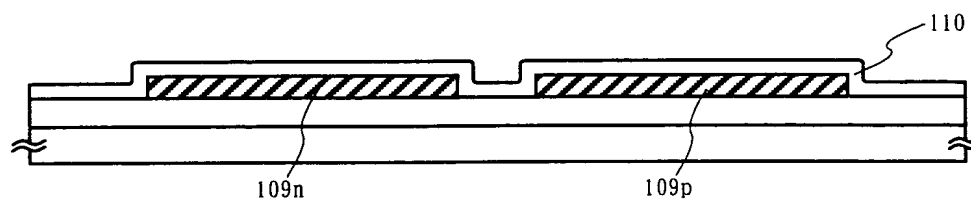


Fig. 2E

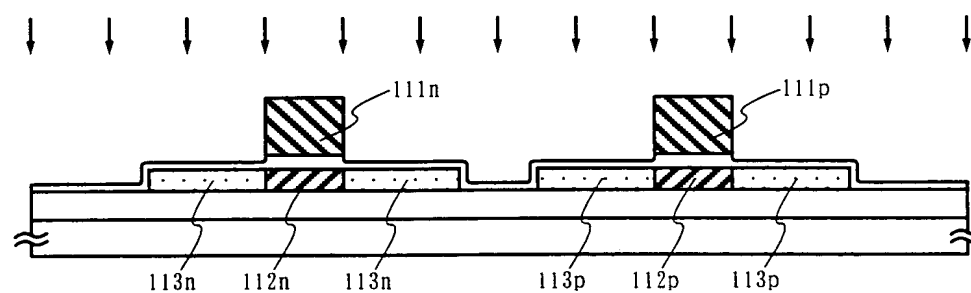


Fig. 3A

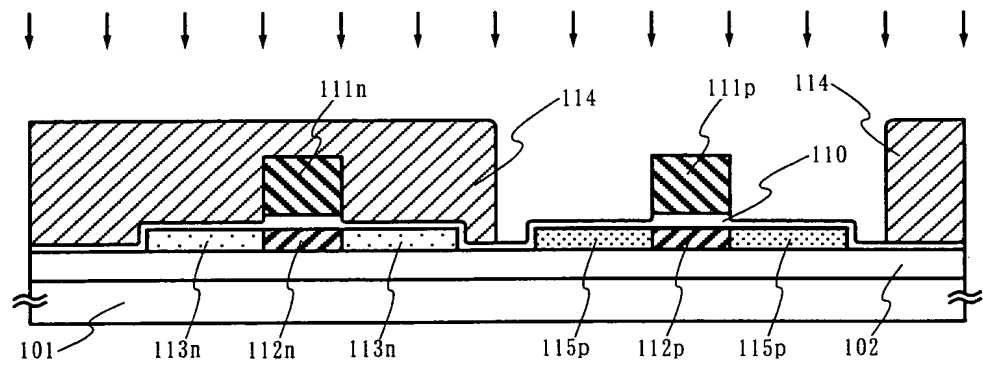


Fig. 3B

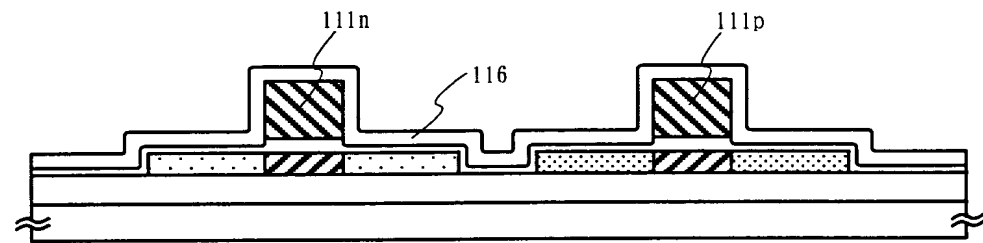


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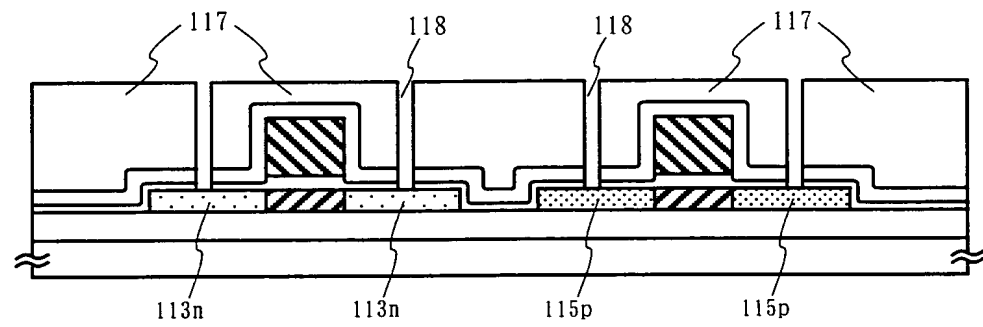


Fig. 3D

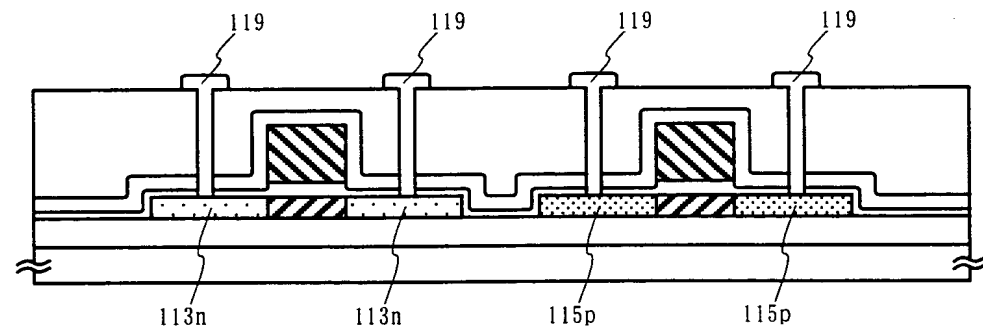


Fig. 4A

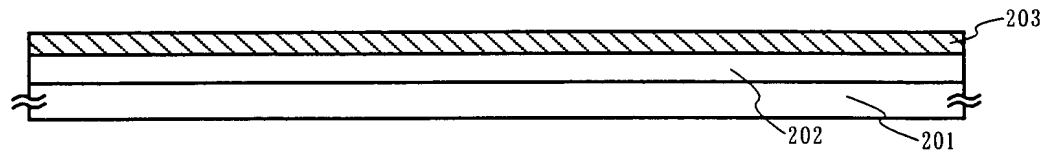


Fig. 4B

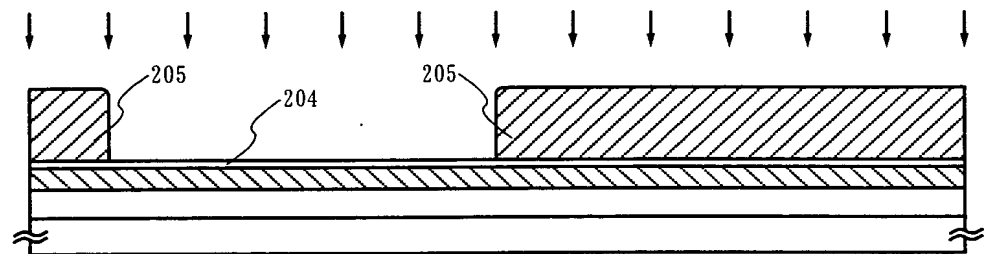


Fig. 4C

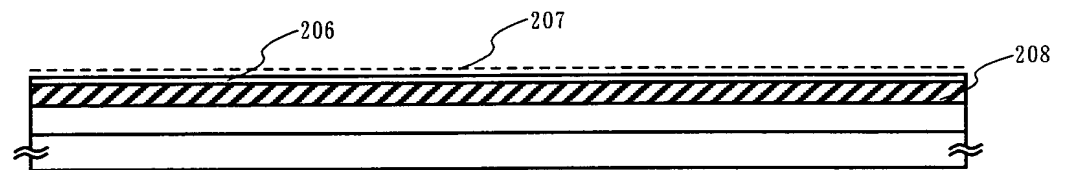


Fig. 4D

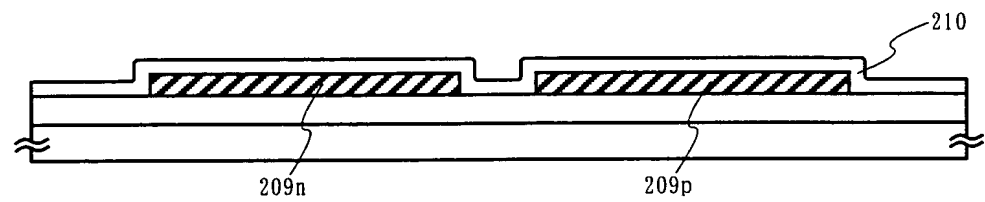
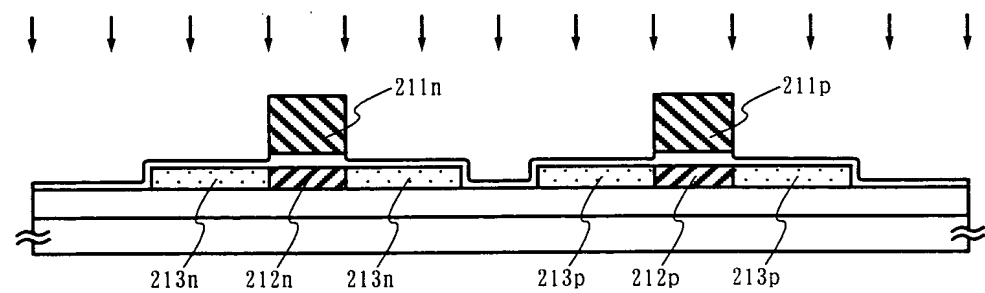


Fig. 4E



201470" 2/22/2007

Fig. 5A

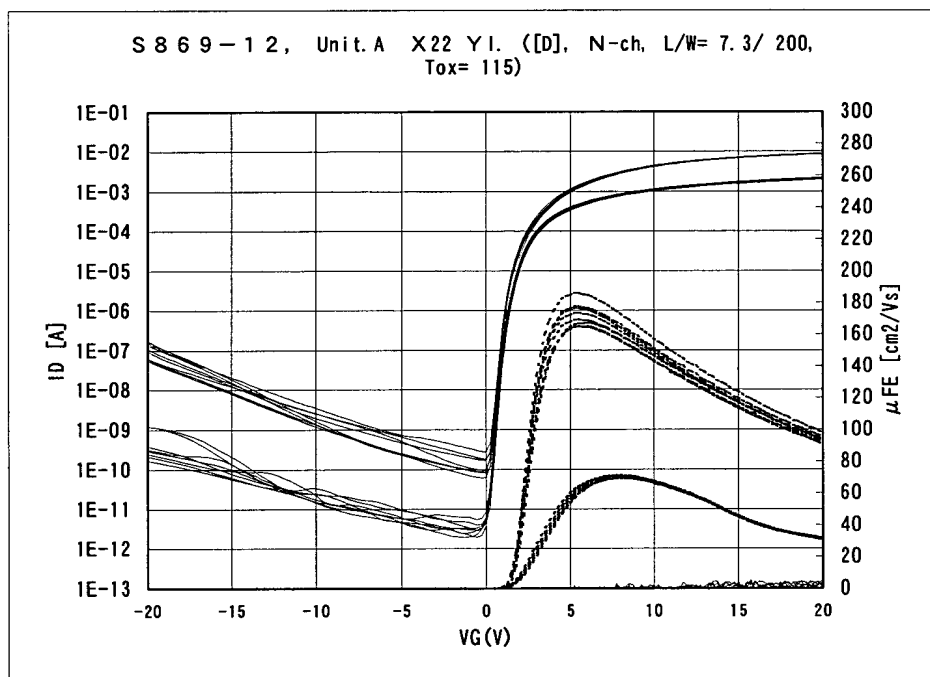


Fig. 5B

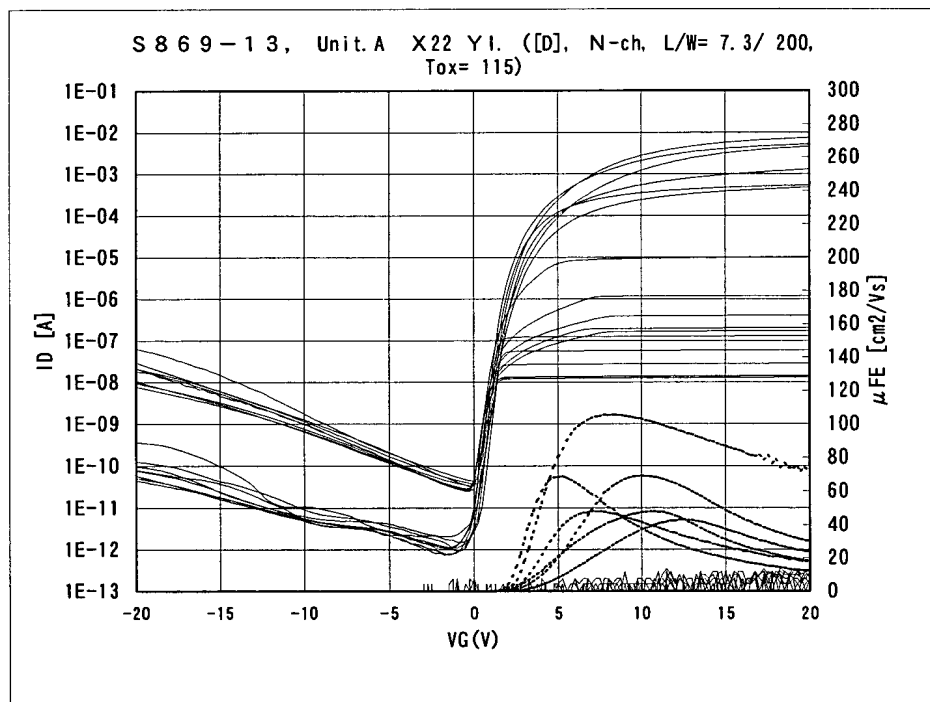


Fig. 6A

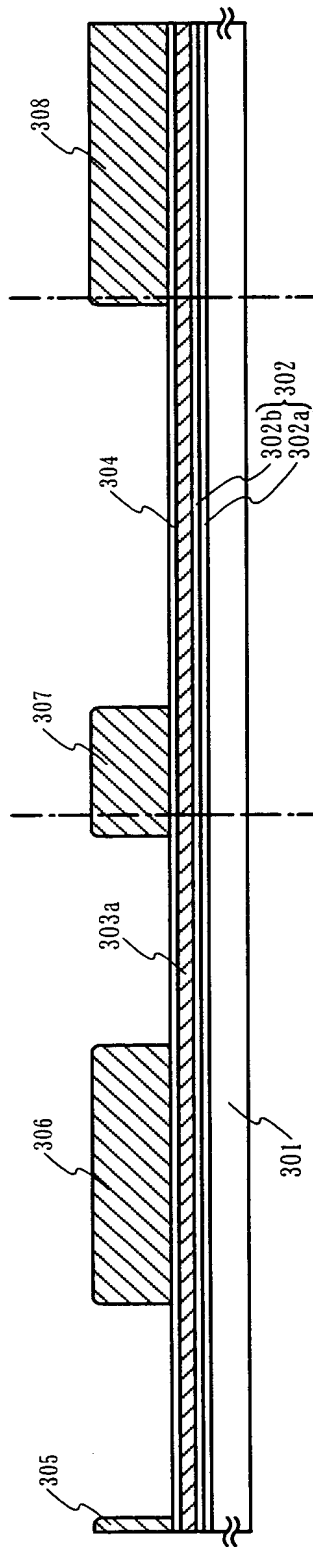


Fig. 6B

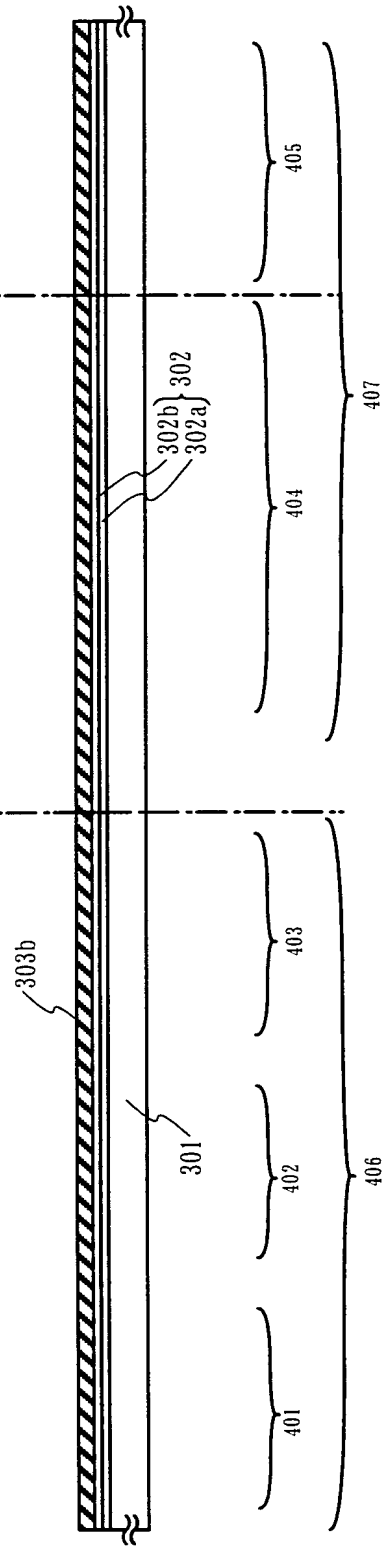


Fig. 7A

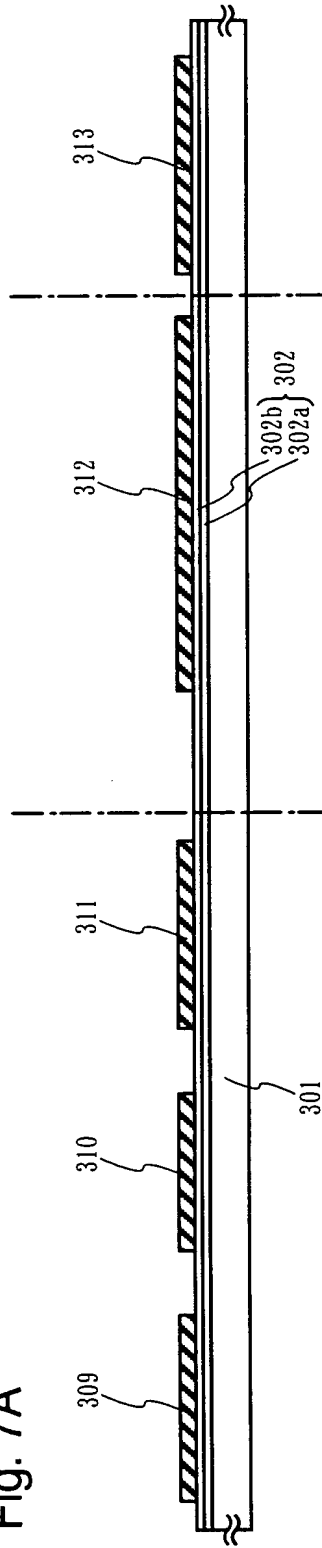
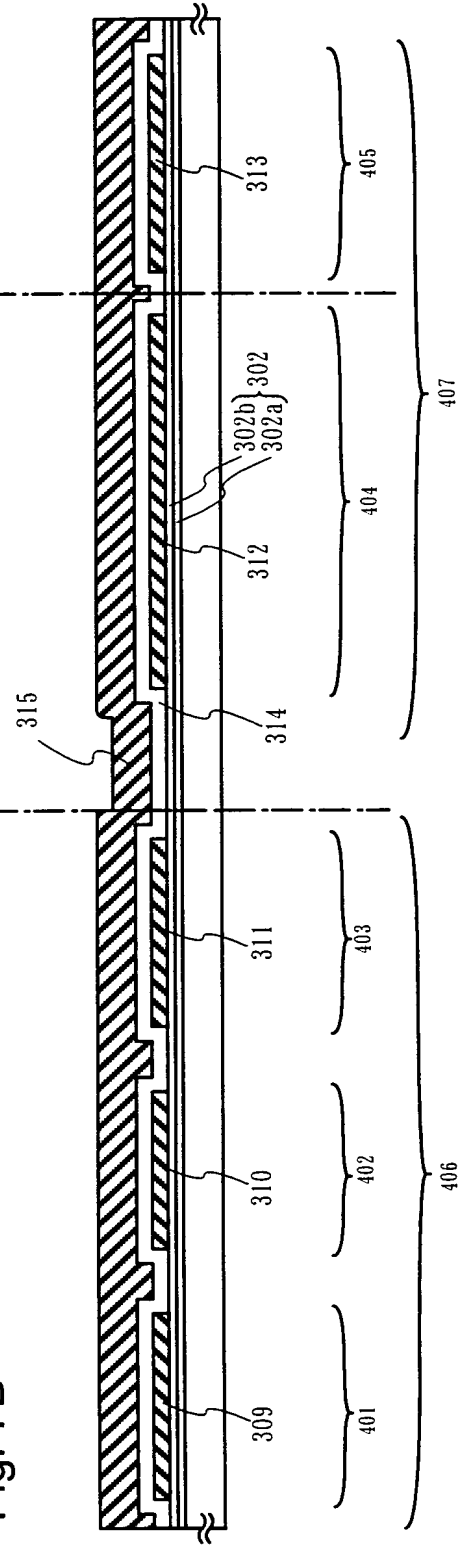


Fig. 7B



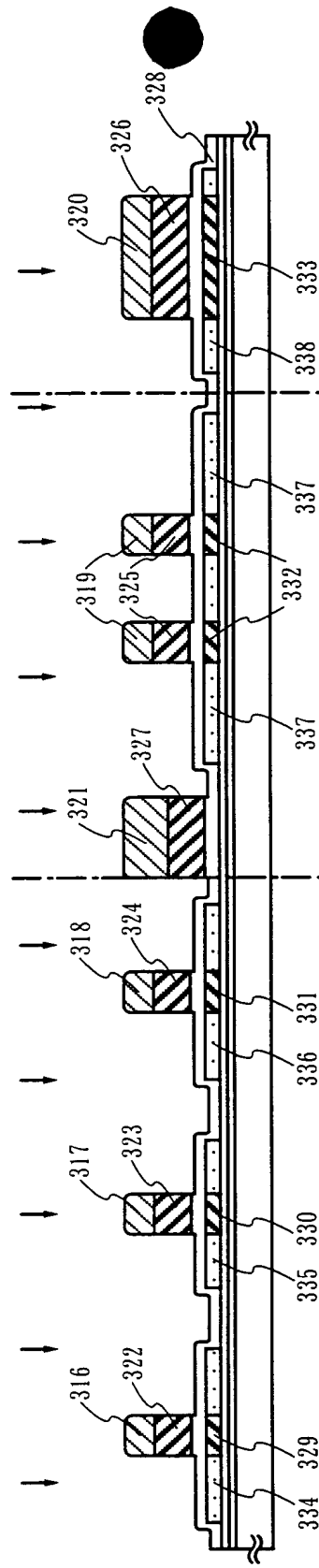


Fig. 8A

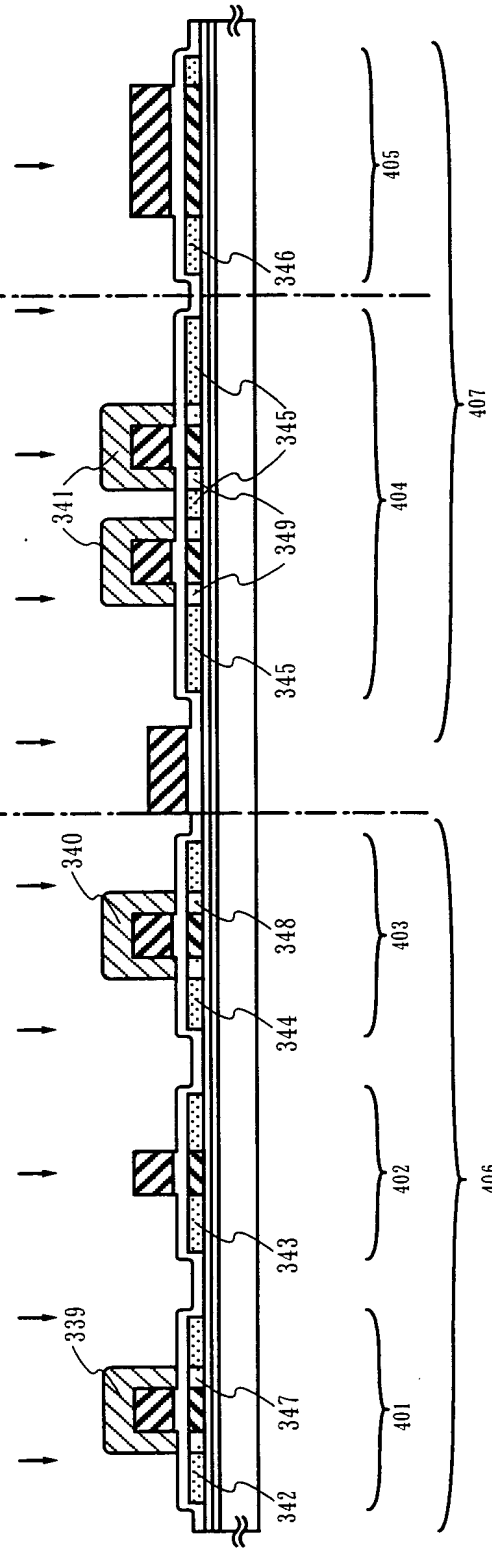


Fig. 8B

Fig. 9A

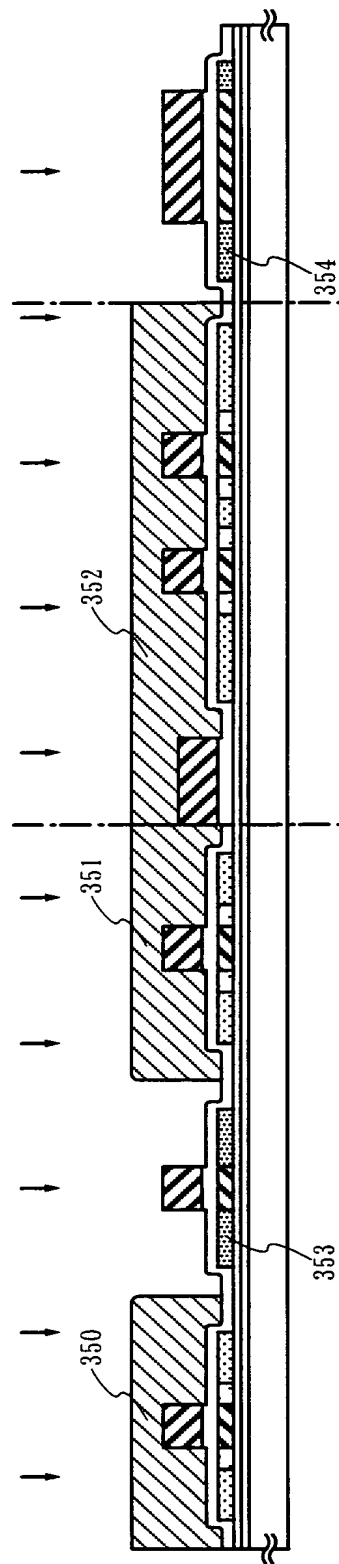
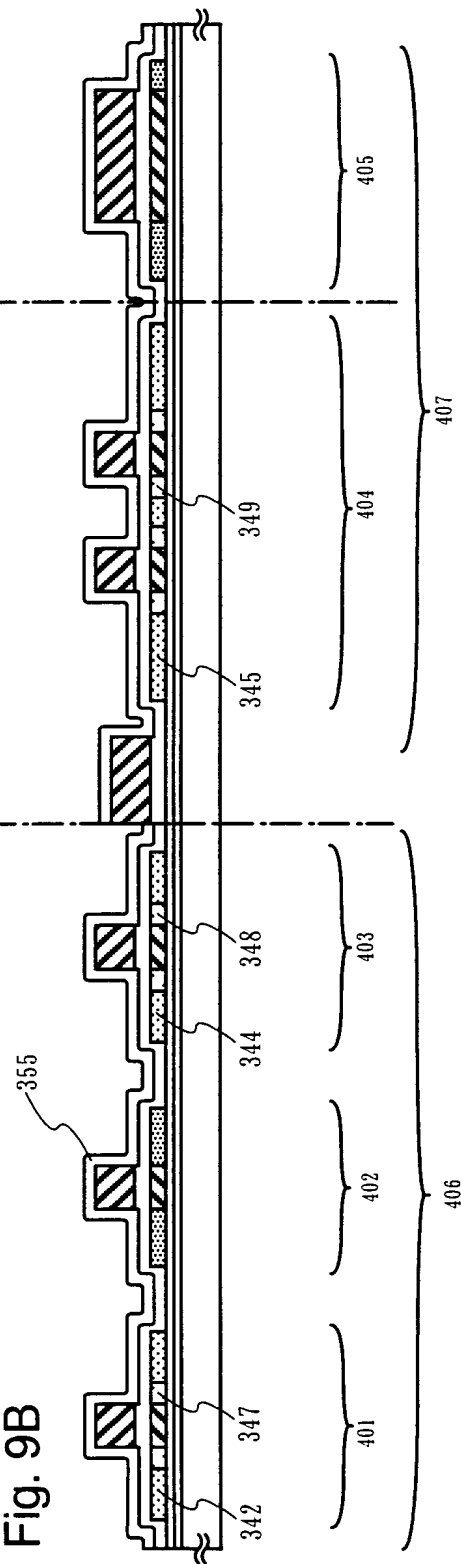


Fig. 9B



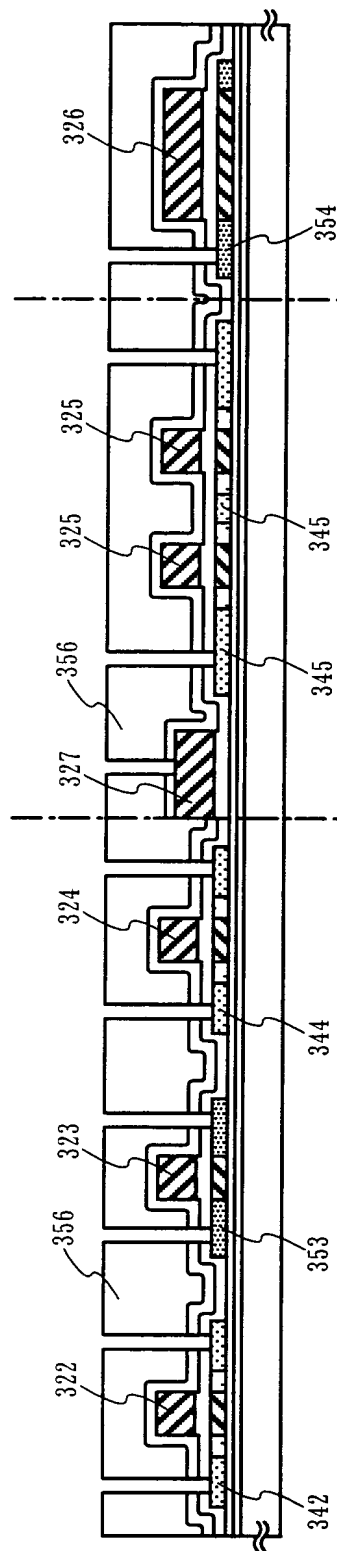


Fig. 10A

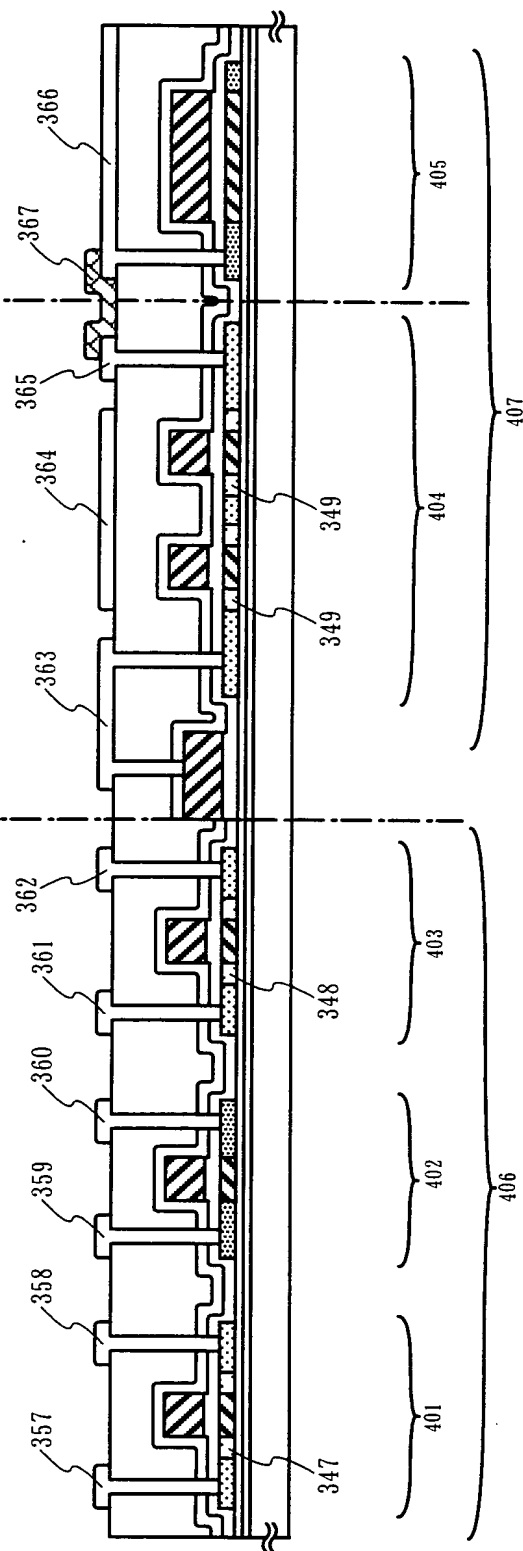


Fig. 10B

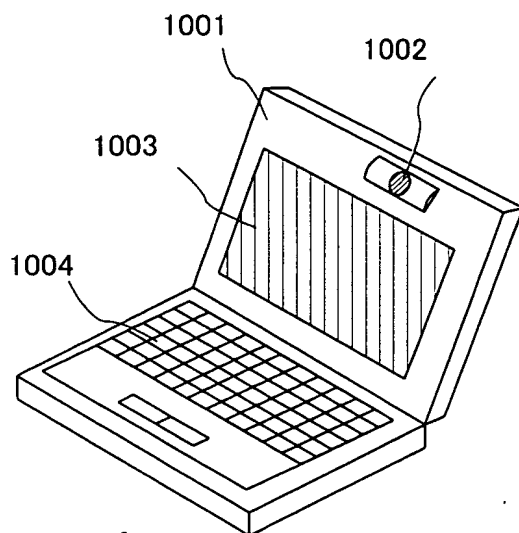


Fig. 11A

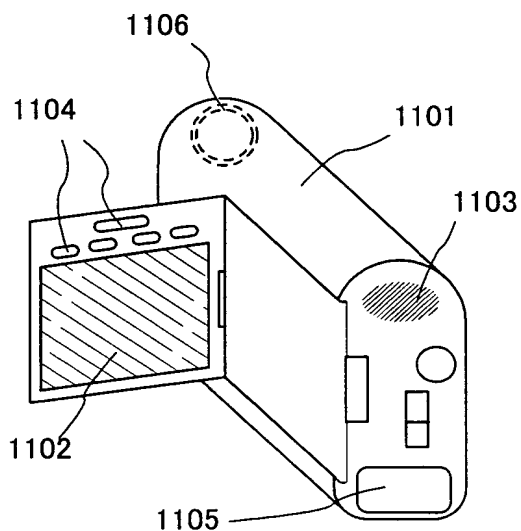


Fig. 11B

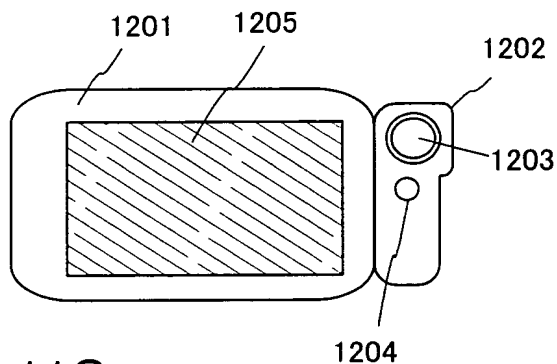


Fig. 11C

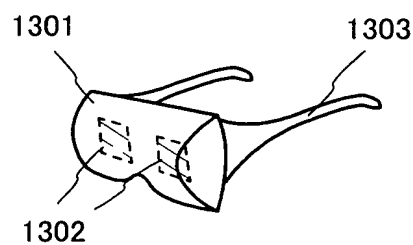


Fig. 11D

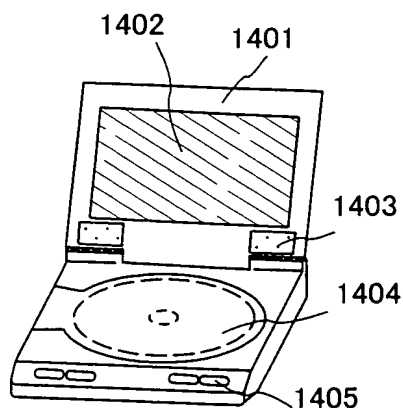


Fig. 11E

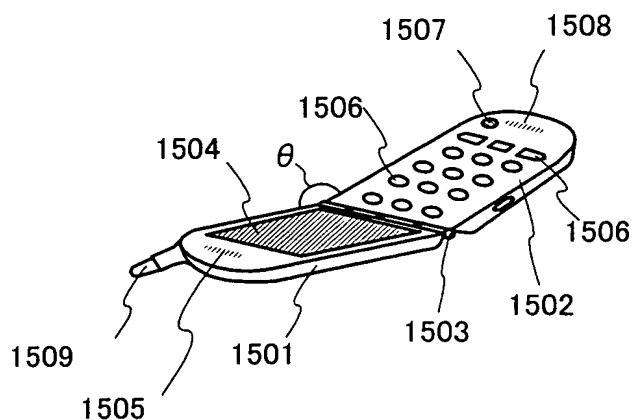


Fig. 11F

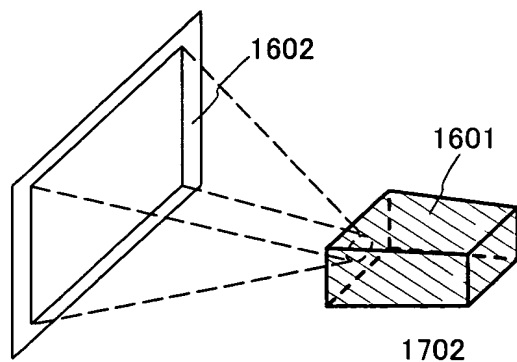


Fig. 12A

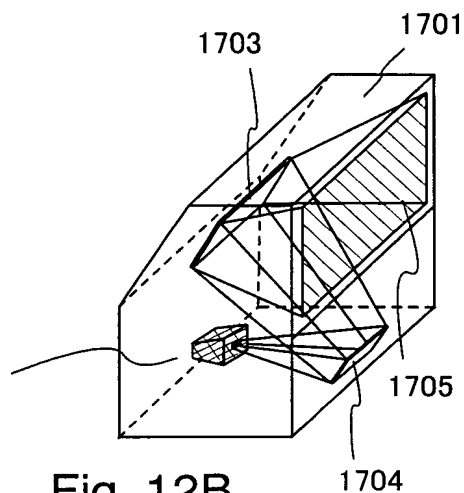


Fig. 12B

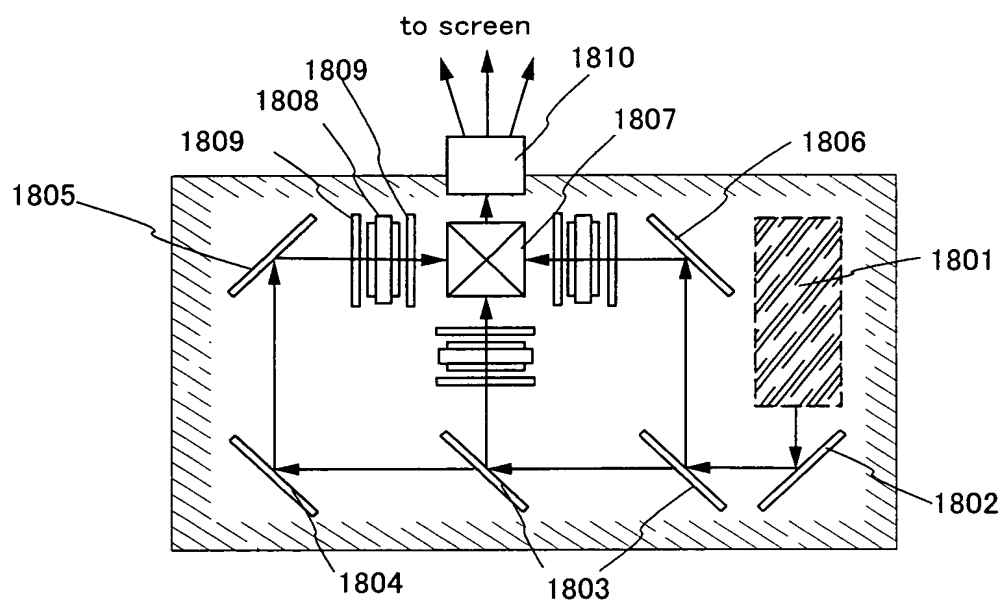


Fig. 12C

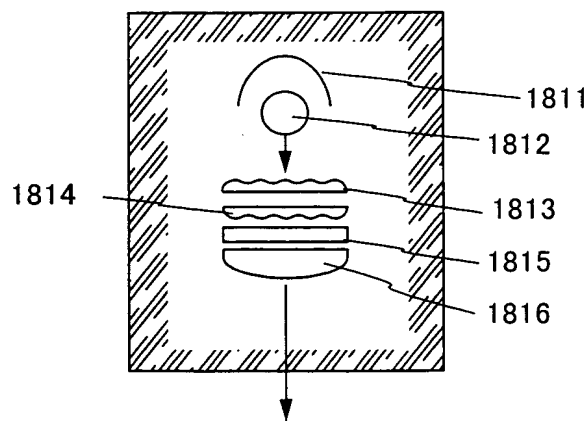


Fig. 12D

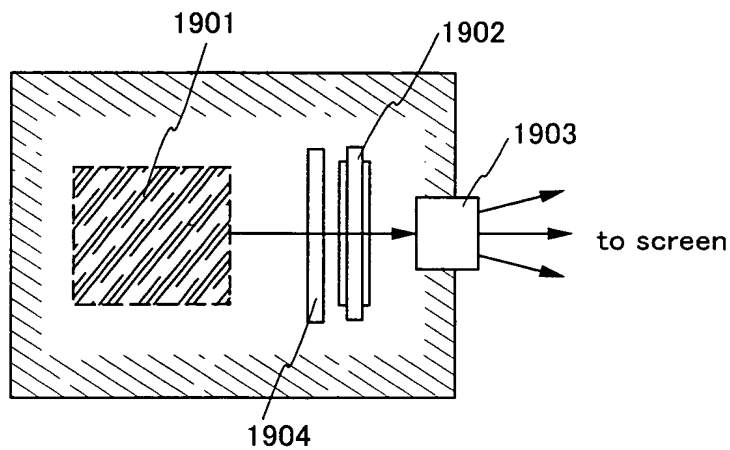


Fig. 13A

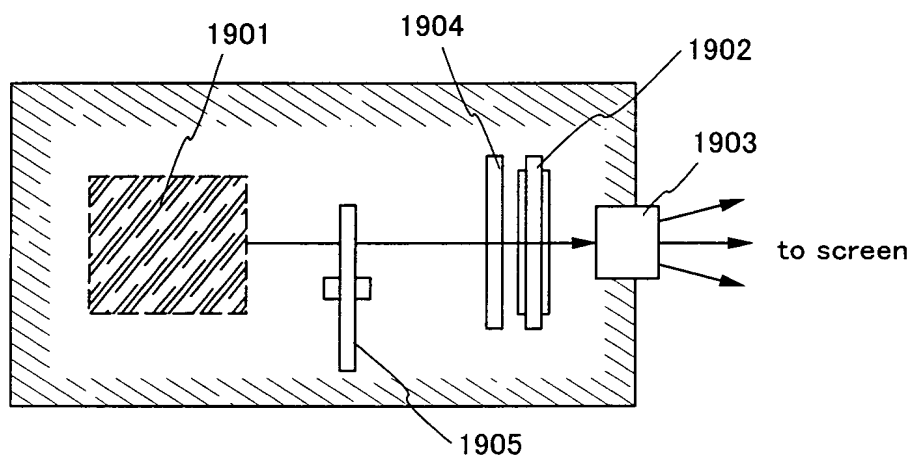


Fig. 13B

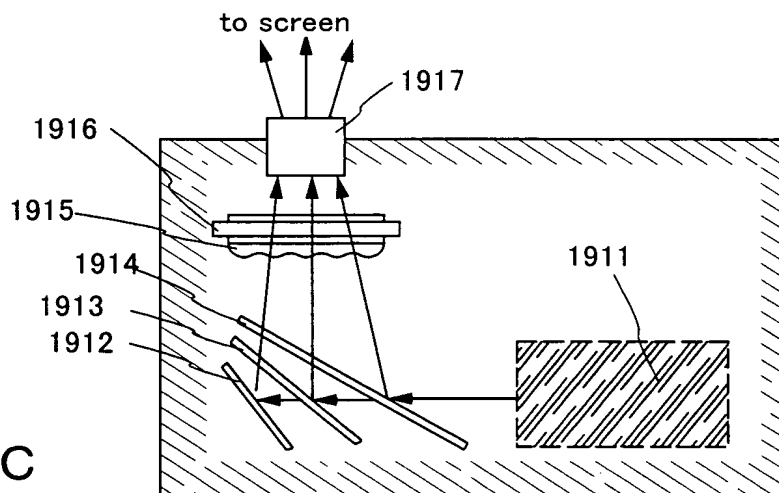


Fig. 13C